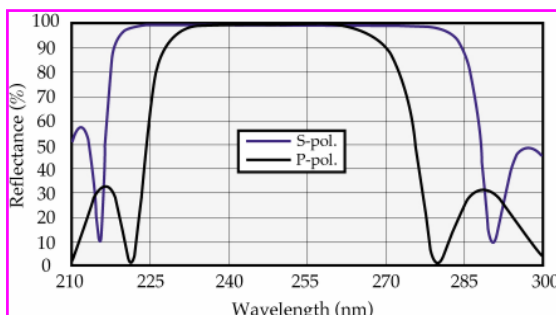


High Power Excimer Laser Mirrors



External mirrors should be made to the same standards as intra-cavity optics. Even outside the cavity, scatter and absorption can cause severe problems in high energy laser systems.

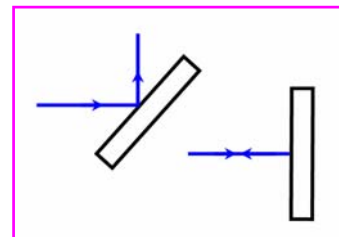


Mirrors are optimized for use at the laser wavelength at either 0° or 45° angle of incidence. They are typically designed to have 99.5% reflectance at 0° or 99.0% minimum reflectance of the p-polarized component at 45°.

Typical Specifications	
Substrate Material:	UVFS, CaF2
Surface flatness:	$\lambda/10$ @ 633 nm
Surface quality:	10/5
Parallelism:	< 3 arcmin
Diameter:	+0.0 / -0.2 mm
Thickness:	± 0.25 mm
Clear aperture:	> 85% of diameter
Reflectance:	R > 99.0%
Damage Threshold:	> 3J/cm ² , 10 ns
Durability:	MIL-C-675

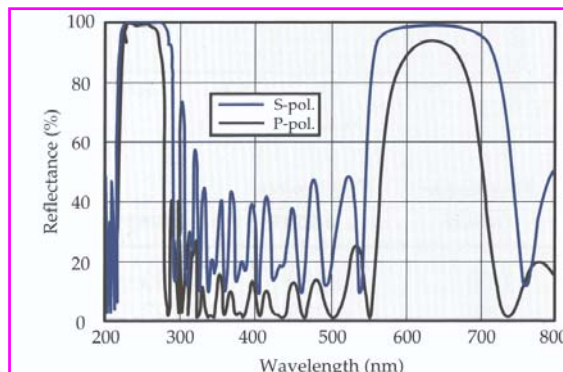
We offer mirrors for the following excimer lasers:

- F₂ 157nm
- ArF 193nm
- KrF 248nm
- XeCl 308nm
- XeF 352nm



Substrates are chosen to be transmissive of the residual energy.

For use with alignment beams a dual wavelength



mirror can be supplied. The second wavelength has a lower, but still useful, reflectivity, typically about 85%.

To request a quote or to order, please specify:

Quantity — Diameter — Laser Type & Wavelength — AOI (0 or 45 deg)

Optarius

PO Box 2271
Malmesbury SN16 9FA
United Kingdom

Optics for the Ultra-Violet

Phone: +44 1666 575185
Fax: +44 1666 577424
Email: optarius@optarius.com
Web: www.optarius.com

For a quotation — please phone, fax or email us with details of your requirements.